

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention

METHOD OF CONFLICT AVOIDANCE IN FABRICATION OF
GATE-SHRINK ALTERNATING PHASE SHIFTING MASKS

Application Number :

Confirmation Number:

First Named Applicant: Lars Liebmann

Attorney Docket Number: FIS920030379

Art Unit:

Examiner:

Search string: (6277527 or 6523165 or 6541165 or 6569583 or 6584610 or 6593038 or 6622288
) .pn

US Patent Documents

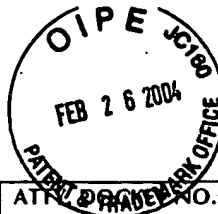
Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
1	1	6277527	2001-08-21	O'Grady et al.			
2	2	6523165	2003-02-18	Liu et al.			
3	3	6541165	2003-04-01	Pierrat			
4	4	6569583	2003-05-27	Cho et al.			
5	5	6584610	2003-06-24	Wu et al.			
6	6	6593038	2003-07-15	Cho et al.			
7	7	6622288	2003-09-16	Wang et al.			

Signature

Examiner Name	Date
<i>A. Porrasco</i>	9/06

SUPPLEMENTAL INFORMATION DISCLOSURE



Sheet 1 of 1

FORM PTO-1449 (Modified)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTORNEY'S NO.: FIS920030379US1	SERIAL NO.: 10/708,055
SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT BY APPLICANT		APPLICANT: Lars W. Liebmann et al.	
(Use several sheets if necessary) (37 CFR 1.98(b))		FILING DATE: 02-05-04	GROUP:

REFERENCE DESIGNATION

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		PATENT NUMBER	ISSUE DATE	PATENTEE	CLASS	SUB- CLASS	FILING DATE IF APPROPRIATE
	AT						
	AU						
	AV						
	AW						
	AX						
	AY						
	AZ						

		U.S. PATENT APPLICATION NO.	PUBLICATION DATE	INVENTOR			
	BA	US2003/0056190A1	03/20/2003	Liu et al.			
	BB						
	BC						
	BD						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY OR PATENT OFFICE	CLASS	SUB- CLASS	TRANSLATION YES NO
	BE						
	BF						
	BG						
	BH						
	BI						

OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)

	Bj	"Alternating Phase Shifted Mask for Logic Gate Levels, Design and Mask Manufacturing", Lars Liebmann, Ioana Graur, William Liepold, James Oberschmidt, David O'Grady and Denis Riegaill, IBM Microelectronics, 12 pages
	BK	
	BL	

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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SUPPLEMENTAL INFORMATION DISCLOSURE

Sheet 1 of 1

FORM PTO 1449 (Modified)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO.: FIS920030379US1	SERIAL NO.: 10/708,055
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		APPLICANT: Lars Liebmann et al.	
Use several sheets if necessary)		FILING DATE: February 5, 2004	GROUP: 1756

REFERENCE DESIGNATION


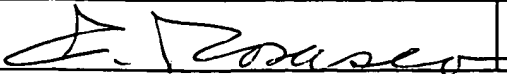
U.S. PATENT DOCUMENTS

EXAMINER INITIAL		PATENT NUMBER	ISSUE DATE	PATENTEE	CLASS	SUB- CLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY OR PATENT OFFICE	CLASS	SUB- CLASS	TRANSLATION YES NO
	AL						
	AM						
	AN						
	AO						
	AP						

OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)

	AQ	"Alternating Phase Shifted Mask for Logic Gate Levels, Design and Mask Manufacturing", Lars Liebmann, Ioana Graur, William Leipold, James Oberschmidt, David O'Grady, Denis Regaill; IBM Microelectronics, East Fishkill, New York and Burlington, Vermont. SPIE Conference on Optical Microlithography XII, March 1999, Vol. 3679, Pages 27-37.
	AR	
	AS	
EXAMINER	DATE CONSIDERED	
		9/06
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance <u>and</u> not considered. Include copy of this form with next communication to applicant.		